

RF MEMS Switches Built on LTCC

(DAD 3.10.05; Activity Responsible: S. Di Nardo)

4th Technical Presentations Day

CTB Working Group on Hybrids, MCMs, interconnection and micropackaging

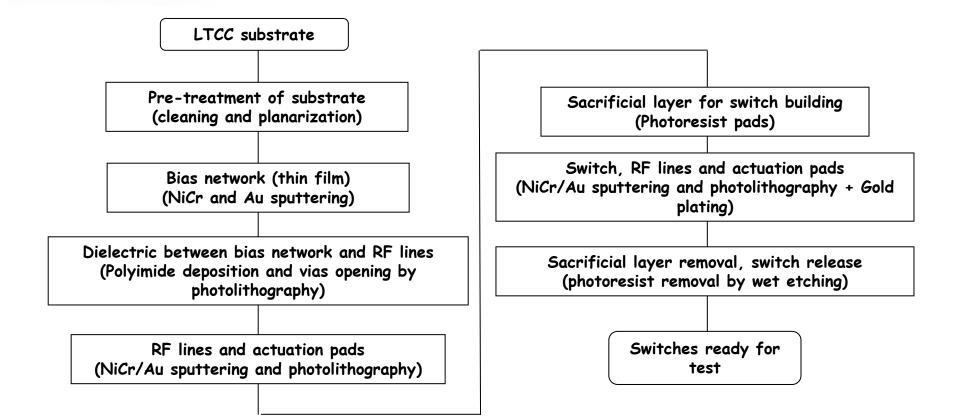
ESA/ESTEC, Noordwijk, 22 May 2007





	02/11/05								_			
tasks	time schedule											
Months: t0	2	4	6	8	10	12	14	16	18	20	22	24
WP1-Reporting of previous experience on LTCC and qualified subtechniques (PID)												
WP2-Definition of the switches to be built	3											
WP3-Design of the dedicated test equipment												
WP4-Manufacturing of MEMS built on LTCC												
WP5-Set-up of the test equipment												
WP6- Electromechanical test												
WP7- Final report												



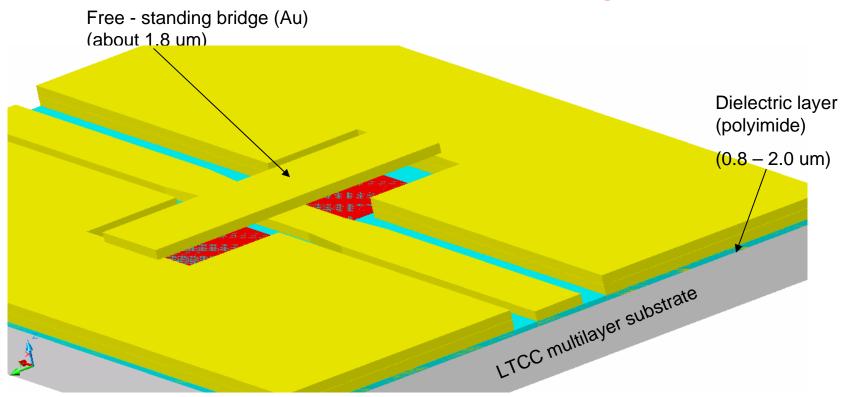


Manufacturing flow



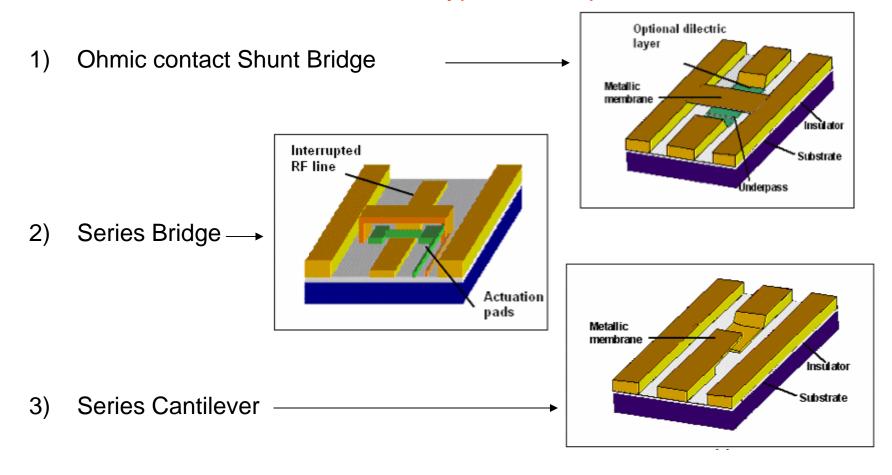


MEMS switch design





Switches types developed

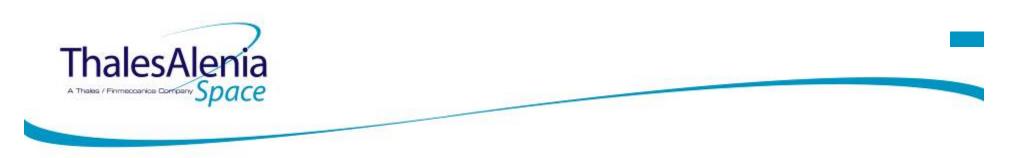




ACTIVITY STATUS

- ☑ kick-off meeting ESTEC/Contract No. 19135/05/NL/PA: 02/11/2005
- ☑ WP1 Reporting of previous experience on LTCC Technology: completed 02/01/06
- ☑ WP2 Definition of the switches to be built: completed 14/03/06
- ☑ WP3 Design of a dedicated test equipment: completed 14/03/06
- WP4 Manufacturing of MEMS built on LTCC: in progress
- ☑ WP5 Set-up of the test equipment: completed 07/04/06
- WP6 Electro mechanical test: in progress
- WP7 Final report

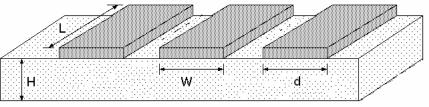
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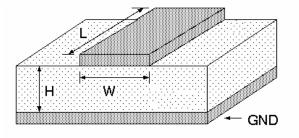


WP4 - Manufacturing of MEMS built on LTCC - LAYOUT:

By the RF point of view the MEM Switches have been manufactured on two different waveguides configurations:

- Coplanar waveguide (CPW)





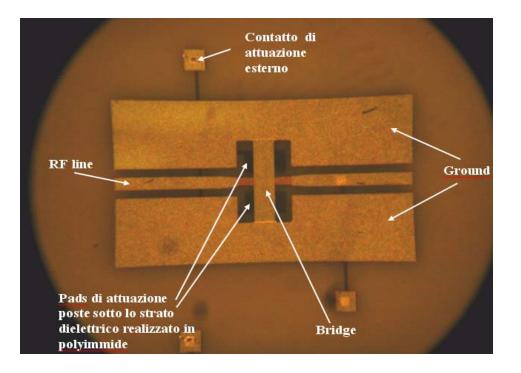
- Microstrip (MS)





WP4 - Manufacturing of MEMS built on LTCC :

CPW configuration: the MEMS shown in the picture represented a bridge standing over a RF line of a coplanar waveguide.



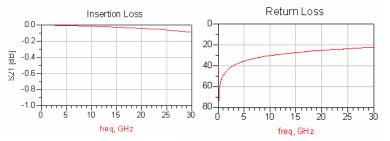


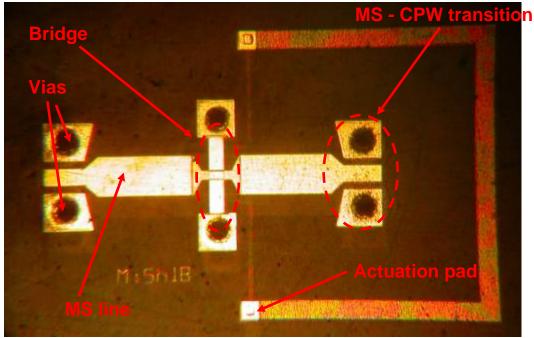


WP4 - Manufacturing of MEMS built on LTCC :

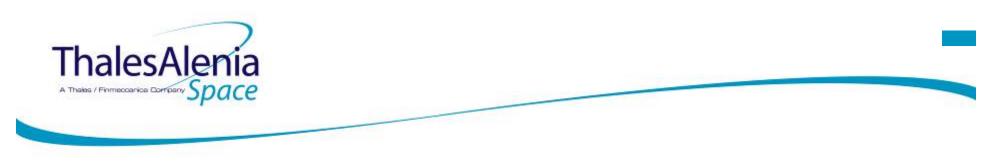
MS configuration: the MEMS shown in the picture represented a bridge standing over a MS line in shunt configuration. CPW/MS transitions have been introduced in order to allow for on-wafer probe measurement.

RF simulation of **MS-CPW** transition:





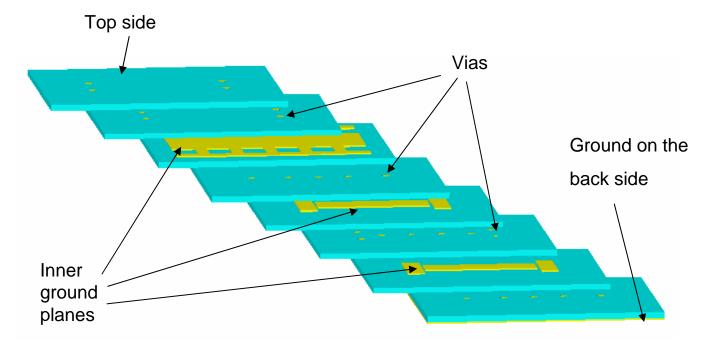




WP4 - Manufacturing of MEMS built on LTCC - LAYOUT:

The MS configuration has been developed on eight layers :

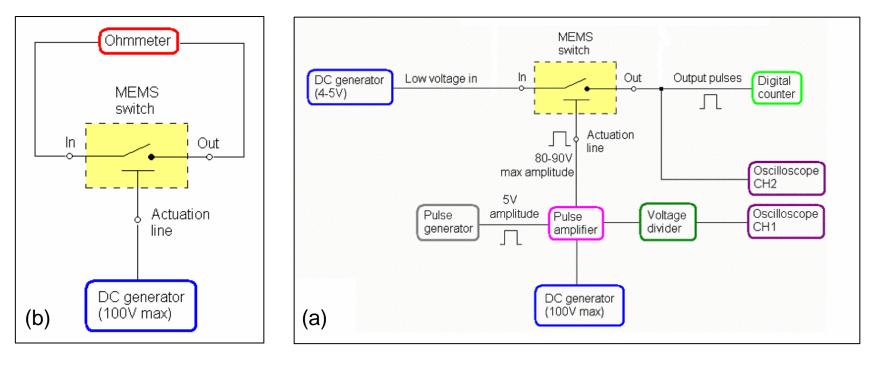
For the microstrip design it has been necessary to place a ground plane at the dept of 274 μ m (between the second and third LTCC layer) and the patterned via holes are used to connect the metal on the surface with the buried ground plane.





WP3 – Design of a dedicated test equipment (DC measurements)

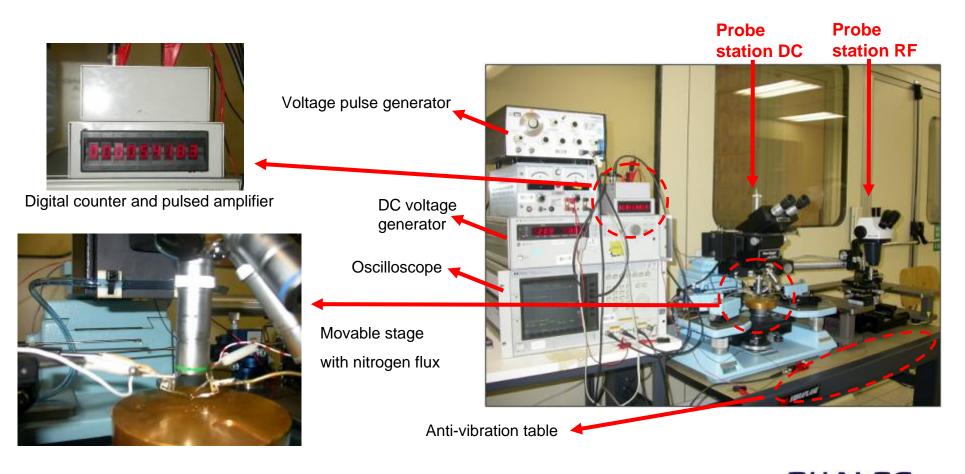
Set-up of static (b) and dynamic (a) tests:



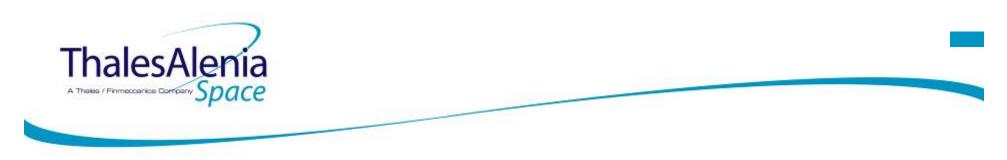




WP5 – Set-up of the test equipment – DC Electromechanical test



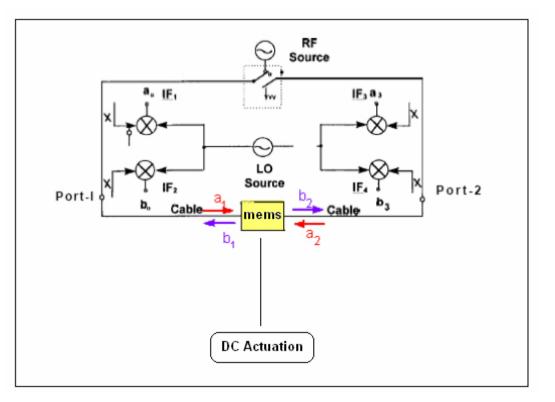
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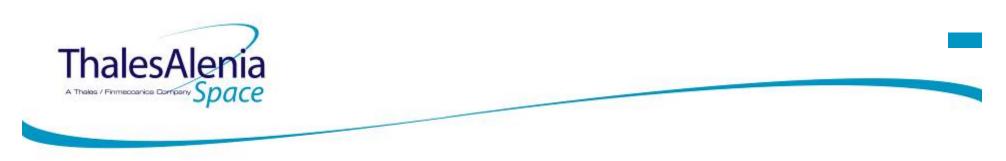


WP3 – Design of a dedicated test equipment (RF measurements)

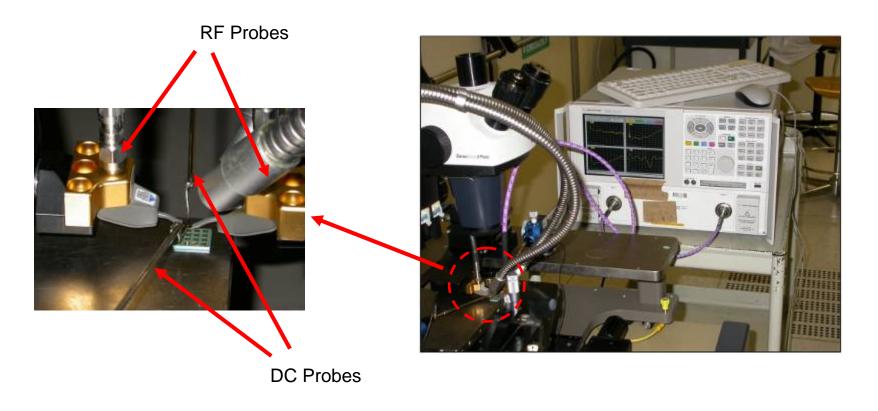
Frequency range of the spectrum analyzer: up to 50GHz

Measurements performed up to 30GHz.





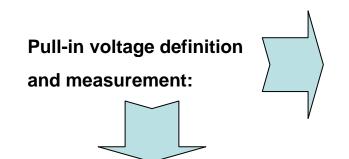
WP5 – Set-up of the test equipment – RF Electromagnetic test

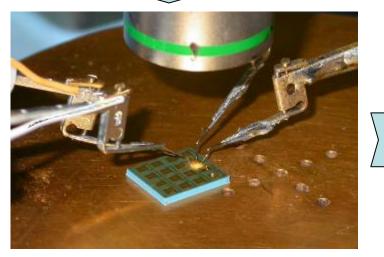


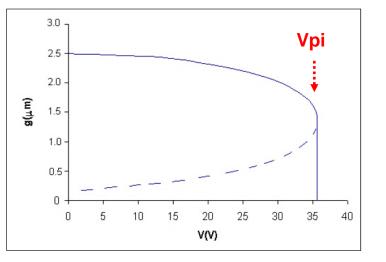




WP6 – Electromechanical test



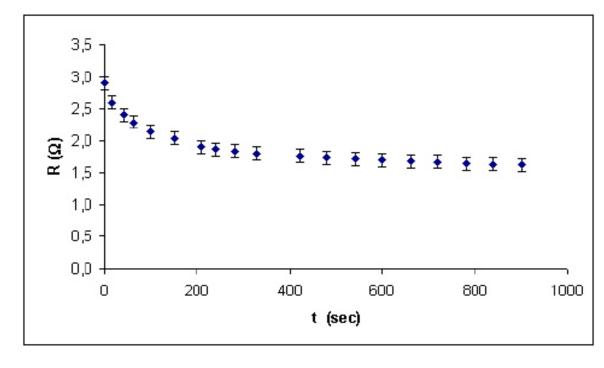




- Pull-in voltage in the range 20V 50V (depending of geometry).
- Contact resistance (gold-gold): 0.2-50hm (TBV)
- No variation of contact resistance have been detected over 10⁵ actuation cycles

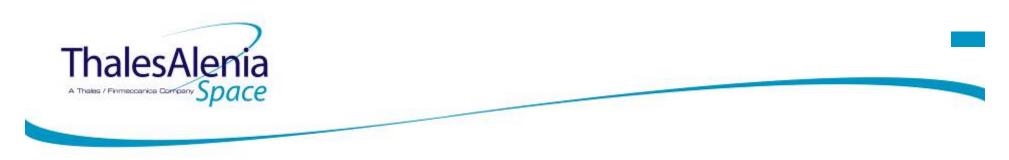


WP6 – Electromechanical test



Static characterization: results after prolonged actuation time:

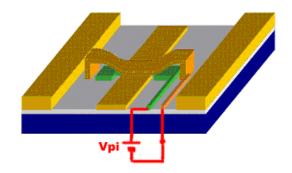
The reduction of the resistance can be explained by an ageing effect

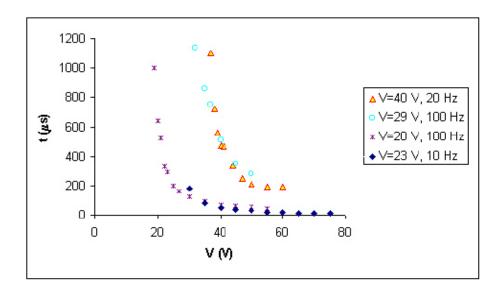


WP6 – Electromechanical test - Dynamic characterization.

The switches have been actuated and de-actuated in a dynamic manner: different behaviors have been detected:

1) The switch follows the pulsed waveform with good behavior: actuation time vs applied voltage are reported below for different devices:





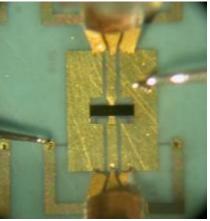
2) The switch doesn't follow the pulsed waveform. Cause under investigation.



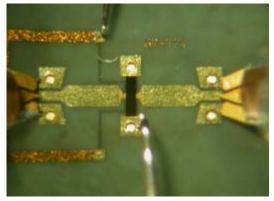
WP6 – Electromagnetic test

Different configurations are under test:

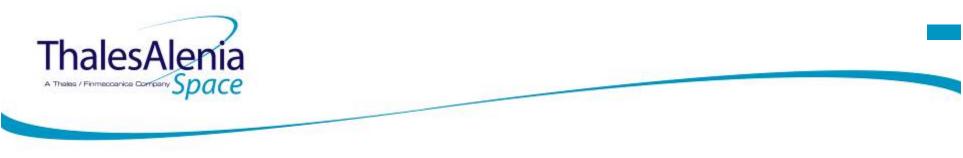
- 1. Shunt switches on CPW
- 2. Shunt switches on MS
- 3. Series switches on CPW



Shunt on CPW



Shunt on MS



Conclusions

- A manufacturing process for MEMS switches on LTCC has been set-up.
- Preliminary electromechanical and electromagnetic tests have shown a fairly good behavior and encouraging results for future developments.
- Pull-in voltage of the manufactured devices are in the range 20-50V.
- Electro mechanical test have to be concluded (milestone 02/10/07)